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Substitute for form 1449A/PTO <b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b> (Use as many sheets as necessary)	Complete if Known	
	Application Number	10/043065
	Filing Date	January 9, 2002
	First Named Inventor	Forbes, Leonard
	Group Art Unit	2822
	Examiner Name	Meier, Stephen
Attorney Docket No: 303.684US3		



Sheet 1 of 1

### US PATENT DOCUMENTS

Examiner Initial*	USP Document Number	Publication Date	Name of Patentee or Applicant of cited Document	Class	Subclass	Filing Date if Appropriate
KR	US-2001/0011744	08/09/2001	Sung, K.	257	314	03/30/2001
	US-2002/0020871	02/21/2002	Forbes, L.	257	315	08/30/2001
	US-2002/0064911	05/30/2002	Eitan, B.	438	216	08/28/2001
	US-3,882,469	05/06/1975	Gosney Jr., William M.	340	173R	06/18/1973
KR	US-5,811,865	09/22/1998	Hodges, Robert L., et al.	257	411	12/16/1996

### FOREIGN PATENT DOCUMENTS

Examiner Initials*	Foreign Document No	Publication Date	Name of Patentee or Applicant of cited Document	Class	Subclass	T <sup>2</sup>
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### OTHER DOCUMENTS -- NON PATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T <sup>3</sup>
KR		SHI, Y., et al., "Tunneling Leakage Current in Ultrathin (<4 nm) Nitride/Oxide Stack Dielectrics", IEEE Electron Device Letters, 19(10), (Oct. 1998), pp. 388-390	

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Substitute Disclosure Statement Form (PTO-1449)

\* EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 909. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. Applicant's unique citation designation number (optional) Applicant is to place a check mark here if English language Translation is attached